



Contribution ID: 178

Type: Poster Presentation

## Synthesis and characterization of sputter deposited TiN thin films

Tuesday, 10 July 2012 17:30 (2 hours)

## Abstract content <br > &nbsp; (Max 300 words)

TiN thin films were deposited on Si<100> substrates and on Cu covered Si substrates by DC magnetron sputtering under varying conditions of power, pressure, argon and nitrogen gas flow rates as well as temperature and characterized by SEM, AFM, RBS, resonant RBS, and XRD. The films were found to adhere well to the substrates. Voltage biasing the films also changes the characteristics of the films. The colour of the films varied depending on deposition conditions and have been expressed in the Lab\* colour system. Potential uses of such films are as protective hard coatings as buffer layers to reduce corrosion.

Apply to be<br/>br> consider for a student <br/> &nbsp; award (Yes / No)?

Yes

Level for award<br/>
-&nbsp;(Hons, MSc, <br>
-&nbsp; PhD)?

Hons

## Main supervisor (name and email)<br/> -br>and his / her institution

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Would you like to <br > submit a short paper <br > for the Conference <br > Proceedings (Yes / No)?

Yes

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Session Classification: Poster Session

Track Classification: Track A - Division for Condensed Matter Physics and Materials